

WEST Search History

DATE: Tuesday, May 20, 2003

Set Name Query

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result set

DB=USPT,PGPB,JPAB,EPAB,DWPI,TDBD; PLUR=YES; OP=ADJ

| | | | |
|----|-----------|---|----|
| L9 | L8 and l6 | 5 | L9 |
|----|-----------|---|----|

| | | | |
|----|--|------|----|
| L8 | (clean\$3 or etch\$3 or treat\$4 or remov\$3) same (substrate or semiconductor or wafer) same ((ammonium fluoride) or 'NH.sub.4F') | 1666 | L8 |
|----|--|------|----|

| | | | |
|----|-----------|---|----|
| L7 | L6 and l5 | 4 | L7 |
|----|-----------|---|----|

| | | | |
|----|---|------|----|
| L6 | ((700/266 700/267 700/268 700/269 700/270 700/271 700/272 700/273 700/274)!.CCLS. (134/56R)!.CCLS. (702/22 702/23 702/24 702/25 702/26 702/27 702/28 702/29 702/30 702/31 702/32)!.CCLS. (436/43 436/50 436/52 436/55 436/100 436/101 436/113 436/124 436/125)!.CCLS. (422/55 422/62 422/82.05 422/187 422/292)!.CCLS.) | 8326 | L6 |
|----|---|------|----|

| | | | |
|----|--|------|----|
| L5 | ((clean\$3 or etch\$3 or treat\$4 or remov\$3) with (substrate or semiconductor or wafer)) same ((ammonium fluoride) or 'NH.sub.4F') with (water or ammonia or 'NH.sub.3') | 1205 | L5 |
|----|--|------|----|

DB=JPAB,EPAB,DWPI; PLUR=YES; OP=ADJ

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|----|------------|---|----|
| L4 | 2000150447 | 2 | L4 |
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DB=JPAB; PLUR=YES; OP=ADJ

| | | | |
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| L3 | JP2000150447 | 1 | L3 |
|----|--------------|---|----|

DB=JPAB,EPAB,DWPI; PLUR=YES; OP=ADJ

| | | | |
|----|--------------|---|----|
| L2 | JP2000150447 | 1 | L2 |
|----|--------------|---|----|

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| L1 | Jp2000-150447 | 0 | L1 |
|----|---------------|---|----|

END OF SEARCH HISTORY

Patent Assignment Abstract of Title

Total Assignments: 1

Application #: 09905662 **Filing Dt:** 07/13/2001 **Patent #:** NONE **Issue Dt:**
PCT #: NONE **Publication #:** 20020046757 **Pub Dt:** 04/25/2001
Inventors: Yasuhito Inagaki, Mineo Shimizu, Yoshihiro Fujitani
Title: Substrate cleaning method and substrate cleaning apparatus

Assignment: 1

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Search Results as of: 5/20/2003 5:03:07 P.M.

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 Web interface last modified: Oct. 5, 2002